

WE CLAIM:

1. A semiconductor device comprising:

an integrated circuit chip having an outline, active  
and passive surfaces, and active components  
including a plurality of contact pads, spaced  
apart by less than 100  $\mu\text{m}$  center to center, on  
said active surface;

a plurality of electrical coupling members attached  
to said contact pads, said coupling members  
selected from a group consisting of gold bumps,  
copper bumps, copper/nickel/palladium bumps, and  
z-axis conductive epoxy;

an electrically insulating thin-film interposer  
having first and second surfaces, a plurality of  
electrically conductive lines integral with said  
first surface, a plurality of electrically  
conductive paths extending through said  
interposer, contacting said conductive lines and  
forming exit ports on said second surface;

said chip coupling members attached to said  
conductive lines, covering an area portion of  
said first interposer surface; and

encapsulation material protecting said passive chip  
surface and at least a portion of said first  
interposer surface not covered by said attached  
chip.

2. The device according to Claim 1 further having solder  
balls attached to said exit ports on said second  
interposer surface.

3. The device according to Claim 1 further having an  
adhesive non-conductive polymer underfilling any spaces

between said chip coupling members attached to said conductive lines under said chip.

4. The device according to Claim 1 wherein said interposer is a polyimide film.

5. The device according to Claim 1 wherein said interposer has an outline larger than said outline of said chip.

6. The device according to Claim 1 wherein said electrically conductive lines are made of a material selected from a group consisting of copper, copper alloy, or copper plated with tin, tin alloy, silver, or gold.

7. The device according to Claim 1 wherein said coupling member attachment is provided by metal interdiffusion of thermo-compression bonding.

8. The device according to Claim 1 wherein said encapsulation material is a molding compound.

9. The device according to Claim 9 wherein said molding compound has the same outline as said interposer.

10. A semiconductor device comprising:

an integrated circuit chip having an outline, active and passive surfaces, and active components including a plurality of contact pads on said active surface;

a plurality of electrical coupling members attached to said contact pads, said coupling members selected from a group consisting of gold bumps, copper bumps, copper/nickel/palladium bumps, and z-axis conductive epoxy;

an electrically insulating thin-film interposer having first and second surfaces, a plurality of electrically conductive lines integral with said first surface, a plurality of electrically

conductive paths extending through said  
interposer, contacting said conductive lines and  
forming exit ports on said second surface;  
said chip coupling members attached to said  
5 conductive lines, covering an area portion of  
said first interposer surface; and  
encapsulation material protecting said passive chip  
surface and at least a portion of said first  
interposer surface not covered by said attached  
10 chip.

11. A method of assembling an integrated circuit device,  
comprising the steps of:

depositing an electrical coupling member of gold,  
copper, or copper/nickel/palladium on each  
15 contact pad of a circuit chip having pads spaced  
apart by less than 100  $\mu\text{m}$ , center to center;  
forming an electrically insulating thin-film  
interposer by depositing and patterning a  
plurality of electrically conductive lines on a  
20 first surface thereof;

creating a plurality of electrically conductive  
paths extending through said interposer;  
contacting said conductive lines on said first  
surface and forming exit ports on a second  
25 surface of said interposer;

assembling the active surface of said chip onto said  
first interposer surface such that each of said  
coupling members is attached to one of said  
lines, respectively, thereby covering an area  
30 portion of said first interposer surface;  
encapsulating, with a polymer compound, the passive  
surface of said chip and at least a portion of

said interposer surface not covered by said  
attached chip, thereby creating a composite  
structure having rigidity; and  
separating the resulting composite structure into  
discrete units.

12. The method according to Claim 11 further comprising the  
step of:

underfilling an adhesive non-conductive polymer into  
any spaces between said chip coupling members  
under said chip, which have been formed by said  
step of assembling said chip onto said  
interposer, thereby strengthening said assembly.

13. The method according to Claim 11 further comprising the  
step of:

attaching solder balls to said exit ports on said  
second interposer surface, after completing said  
step of encapsulating and before said step of  
separating.

14. The method according to Claim 11 wherein said step of  
depositing comprises plating, electro-plating,  
sputtering, or evaporating.

15. The method according to Claim 11 wherein said step of  
separating comprises the steps singulating, trimming  
and forming said composite structure.

16. The method according to Claim 11 wherein said step of  
assembling comprises the method of thermo-compression  
gang bonding said chip coupling members onto said  
interposer lines.